

Since I see 12 students enrolled in F8542 Experimentální metody a speciální praktikum A 2, please, confirm who really will need to do the measurement and, therefore, will come on Tuesday. It's clear that Pekař, Procházka, Studnička, Tesař don't need a new measurement because they measured it the last school year. Shall I really expect 8 students coming?

thermal SiO<sub>2</sub>

- reflectance in UV/VIS

fit of R by own program expecting normal incidence and  $k=0$

organosilicon plasma polymer

- reflectance in UV/VIS
- transmittance in IR

fit of R by own program expecting normal incidence and

a)  $k=0$  or

b) exponential form of  $k$ , i.e.  $k=c*\exp(-d*\lambda)$

Comparison of results a) and b)

c) assignment of peaks in IR range

diamond like carbon (DLC)

- reflectance in UV/VIS
- ellipsometry
- transmittance in IR

a) fit of R by own program expecting normal incidence and exponential form of  $k$ , i.e.  $k=c*\exp(-d*\lambda)$

b) calculation of complex dielectric function from ellipsometric measurement assuming semiinfinite sample

c) fit of R and ellips together by program newAD using dispersion formula based on parametrization of density of states

d) assignment of peaks in IR range

TiC films prepared by magnetron sputtering

- ellipsometry

calculation of complex dielectric function from ellipsometric measurement assuming semiinfinite sample